

Search Notes**Application No.**

10/720,851

Examiner

Stephen W. Smoot

Applicant(s)

UESAWA, FUMIKATSU

Art Unit

2813

SEARCHED			
Class	Subclass	Date	Examiner
438	620	6/25/2004	SWS
438	637	6/25/2004	SWS
438	640	6/25/2004	SWS
438	669	6/25/2004	SWS
438	671	6/25/2004	SWS
438	673	6/25/2004	SWS
438	780	6/25/2004	SWS
Updated	Above	12/6/2004	SWS
438	978	12/6/2004	SWS

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner

SEARCH NOTES (INCLUDING SEARCH STRATEGY)		
	DATE	EXMR
Key Words: Mask - Organic, Tapered, Photoresist, Resist, Aperture, Hole Opening;	6/25/2004	S.W.S.
Dual Hard Mask; Low Temperature Etching.	6/25/2004	S.W.S.
Updated Above Search	12/6/2004	S.W.S.
Search Tools - EAST (attached); USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	6/25/2004 12-6-04	SWS S.W.S.